

Inventor: Brian A. Vaartstra
Title: Aluminum-Containing Material and Atomic Layer Deposition Methods
Assignee: Micron Technology, Inc.
Docket No. MI22-2489

INFORMATION DISCLOSURE STATEMENT
PURSUANT TO 37 C.F.R. §§ 1.56, 1.97 AND 1.98

In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449. No admission is made regarding whether all the submitted references are prior art.

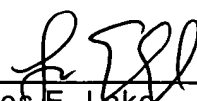
Most of the listed references were cited by, or submitted to, the Office in the parent, co-pending application of the above-identified application. The above-identified application is a continuation application of co-pending application Serial No. 10/099,624, filed March 14, 2002. Such prior disclosure is sufficient for the above-identified application as far as copies of the references are concerned. 37 C.F.R. § 1.98(d) and MPEP § 609(2). Other copies of the cited art not included are U.S. patents. (1276 Off.Gaz.Pat.Off., 05 Aug. 2003).

Citation of these references is respectfully requested.

Respectfully submitted,

Dated: 13 Apr 2004

By:


James E. Lake
Reg. No. 44,854

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		Priority ATTY. DOCKET NO. MI22-1830	Priority SERIAL NO. 10/099,624		
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Brian A. Vaartstra			
				Priority FILING DATE March 14, 2002	Priority GROUP 1765		
U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	5,908,947	06/1999	Vaartstra			
	AB	6,287,965	09/2001	Kang et al			
	AC	6,391,803	05/2002	Kim et al			
	AD	5,840,897	11/1998	Kirlin et al			
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes No
	AM	2002027063	04/2002	PCT/Gordon et al			
	AN						
	AO						
	AP						
	AQ						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AR		Sean T. Barry, et al, "Monomeric Chelated Amides of Aluminum and Gallium: Volatile, Miscible Liquid Precursors for CVD", Harvard University Chemical Laboratories, Mater. Res. Soc. Symp. Proc., 2000, Vol. 606, pg. 83				
	AS		Kim et al., "Compositional Variations of TiAlN Films Deposited by Metalorganic Atomic Layer Desposition Method", Jpn. J. Applied Physics, vol. 41, part 1 (2a) 2-2002, pages 562-565.				
	AT						
EXAMINER				DATE CONSIDERED			
<small>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>							